

L Number	Hits	Search Text	DB	Time stamp
1	2898	plasma adj density	USPAT	2004/02/05 09:08
2	1911	(plasma adj density) and semiconductor	USPAT	2004/02/05 09:09
3	1018	((plasma adj density) and semiconductor) and (oxygen or O?sub.2)	USPAT	2004/02/05 09:09
4	545	((plasma adj density) and semiconductor) and (oxygen or O?sub.2)) and (photo\$1resist or resist)	USPAT	2004/02/05 09:10
5	12	Ishihara-Shigenori.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/02/05 11:00
8	2225	(resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)	USPAT	2004/02/05 11:31
9	6	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine near4 "%")	USPAT	2004/02/05 11:02
10	1343	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)	USPAT	2004/02/05 11:04
14	1100	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000	USPAT	2004/02/05 11:05
15	578	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000) and (dope or doping or dopant or implant\$3 or implantation)	USPAT	2004/02/05 11:13
16	142	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and (fluorine or CF?sub.4 or SF?sub.6)) and plasma and @ay<=2000) and (dope or doping or dopant or implant\$3 or implantation)) and (photo\$1resist or resist or photo\$1sensitive).ab.	USPAT	2004/02/05 11:14
17	5	("4511430" "5226056" "5503964" "5795831" "5811358").PN.	USPAT	2004/02/05 11:27
18	15	("4123841" "4514254" "4670091" "4983254" "5077598" "5122225" "5348619" "5358602" "5451291" "5485304" "5497262" "5512507" "5521104" "5526951" "5573971").PN.	USPAT	2004/02/05 11:30
19	80	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and ((fluorine\$ or CF?sub.4 or SF?sub.6) with (percent or "%" or percentage))	USPAT	2004/02/05 11:31
20	71	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)) and ((fluorine\$ or CF?sub.4 or SF?sub.6) with (percent or "%" or percentage))) and @ay<=1999	USPAT	2004/02/05 11:32
-	3838	(resist or photo\$1resist) same (ash or ashing)	USPAT	2004/01/14 13:41
-	2210	(resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2)	USPAT	2004/02/05 11:01
-	2412	(resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))	USPAT	2004/01/14 13:44
-	1045	((resist or photo\$1resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)	USPAT	2004/01/14 13:45

247	((semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$1implant\$3 or doped or doping or dopant)) and plasma) and (resist or photo\$1resist or photo\$1sensitive or organic)	USPAT	2004/01/21 15:22
238	((semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$1implant\$3 or doped or doping or dopant)) and plasma) and (resist or photo\$1resist or photo\$1sensitive or organic)) and @ay<=2001	USPAT	2004/01/21 15:21
206	((semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$1implant\$3 or doped or doping or dopant)) and plasma) and (resist or photo\$1resist or photo\$1sensitive)	USPAT	2004/01/21 15:23
20	("4778536" "5100505" "5108542" "5147499" "5160765" "5200361" "5296093" "5298112" "5485754" "5628871" "5693147" "5744192" "5773201" "5810929" "5814155" "5851302" "5882489" "5895274" "5925577" "6066508").PN.	USPAT	2004/01/21 15:43
8	("5034086" "5226056" "5393374" "5567271" "5792314" "5902134" "6024887" "6043004").PN.	USPAT	2004/01/21 16:41
3173	(resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)	USPAT	2004/02/02 11:02
2039	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma	USPAT	2004/02/02 11:01
947	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)	USPAT	2004/02/02 11:01
768	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))	USPAT	2004/02/02 11:06
515	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$1implant\$3)	USPAT	2004/02/02 11:12
497	((resist or photo\$1resist or photo\$1sensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$1implant\$3)) and @ay<=2001	USPAT	2004/02/02 11:05

-	474	(((((resist or photo\$iresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$implant\$3)) and @ay<=2001) and semiconductor	USPAT	2004/02/02 11:05
-	301	(((((resist or photo\$iresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$implant\$3) same (resist or photo\$iresist or photo\$lsensitive))	USPAT	2004/02/02 11:13
-	163	(((((resist or photo\$iresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$implant\$3) with (resist or photo\$iresist or photo\$lsensitive))	USPAT	2004/02/02 11:13
-	156	(((((resist or photo\$iresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$implant\$3) with (resist or photo\$iresist or photo\$lsensitive))) and @ay<=2001	USPAT	2004/02/02 11:14
-	145	(((((resist or photo\$iresist or photo\$lsensitive) same (oxygen\$ or O?sub.2) same (hydrogen\$ or H?sub.2)) and plasma) and (fluorine or F?sub.2 or fluoride)) and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2))) and (implant\$3 or doping or dopant or doped or ion\$implant\$3) with (resist or photo\$iresist or photo\$lsensitive))) and @ay<=2000	USPAT	2004/02/02 11:14
-	16	("4063803" "4201579" "4340456" "4817558" "4990229" "5122251" "5262610" "5366557" "5397395" "5429070" "5542559" "5625259" "5747917" "5789322" "5824604" "5895548").PN.	USPAT	2004/02/02 11:16
-	8	("5034086" "5226056" "5393374" "5567271" "5792314" "5902134" "6024887" "6043004").PN.	USPAT	2004/02/02 11:35

-	970	((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma	USPAT	2004/01/14 13:45
-	593	(((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6"))	USPAT	2004/01/14 13:47
-	402	(((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6)	USPAT	2004/01/14 13:49
-	348	(((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6) and @ay<=2000	USPAT	2004/01/14 13:50
-	344	((((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6) and @ay<=2000 and (boron or phosphorus or arsenic or As!))	USPAT	2004/01/14 13:51
-	101	((((((resist or photo\$!resist) same (ash or ashing) same (oxygen or O?sub.2 or CO or NO or (nitrogen adj oxide))) and (doping or dopant or implant or implanting or implanted)) and plasma) and (hydrogen or H?sub.2 or "H.sub.2 O" or CH?sub.4 or "C.sub.2 H.sub.6")) and (fluorine or fluoride or NF?sub.3 or F?sub.2 or SF?sub.6) and @ay<=2000) and (boron or phosphorus or arsenic or As!)) and plasma.ab.	USPAT	2004/01/14 13:52
-	14	("4296146" "4778536" "4861424" "4944837" "5013366" "5037506" "5298112" "5382316" "5401322" "5403436" "5643474" "5651860" "6024801" "6149828").PN.	USPAT	2004/01/14 14:50
-	657	semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))	USPAT	2004/01/21 15:16
-	360	(semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$!implant\$3 or doped or doping or dopant)	USPAT	2004/01/21 15:19
-	322	((semiconductor and ((oxygen\$ or O?sub.2) with (hydrogen\$ or H?sub.2) with (fluorine\$))) and (implant\$3 or ion\$!implant\$3 or doped or doping or dopant)) and plasma	USPAT	2004/01/21 15:19